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Form 1449*

Applicant: Fernando Gonzalez

Filing Date: August 30, 2001

Group: 2811

U.S. PATENT DOCUMENTS

**Examiner Filing Date
Initial Document Number Date Name Class Subclass If Appropriate

FOREIGN PATENT DOCUMENTS

Initial	Document Number	Date	Country	,	Class	Subclass	Yes No
**Examiner Initial	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
040	Technologi		nd", <u>Sym</u>	Shallow Trench i posium on VLSI Te			
010	Goebel, B., et al., "Vertical N-Channel MOSFETs for Extremely High Density Memories: The Impact of Interface Orientation on Device Performance", IEEE Transactions on Electron Devices.48(5) , pp. 897-906, (May 2001)						
040	Matsuda, S., et al., "Novel Corner Rounding Process for Shallow Trench /Isolation utilizing MSTS (Micro-Structure Transformation of Silicon)", IEDM, pp. 137-140, (1998)						
240	Uh, H., et 0.12microm <u>Papers</u> , 2	al., "A S eter Design pages, (2	trategy : Rule", §	for Long Data Ret Symposium on VLSI ,	ention T Technol	ime of 51 ogy Diget	2Mb DRAM with s of Technical

Examiner Dough & Owen	Date Considered 5/15/03
*Substitute Disclosure Statement Form (PTO-1449)	